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PATENT NUMBER

O.I.P.E.

PATENT DATE

SCANNED *JL2* Q.A.

APPLICANTS

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Positive-working photoresist composition and resist patterning method using same

PTO-2040
12/89

ORIGINAL

CROSS REFERENCE(S)

CLASS

SUBCLASS

CLASS

SUBCLASS (ONE SUBCLASS PER BLOCK)

INTERNATIONAL CLASSIFICATION

Continued on Issue Slip Inside File Jacket

<input type="checkbox"/> TERMINAL DISCLAIMER	DRAWINGS			CLAIMS ALLOWED	
	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.
<input type="checkbox"/> The term of this patent subsequent to _____ (date) has been disclaimed.	_____ (Assistant Examiner) (Date)			NOTICE OF ALLOWANCE MAILED	
<input type="checkbox"/> The term of this patent shall not extend beyond the expiration date of U.S. Patent. No. _____ _____ _____	_____ (Primary Examiner) (Date)			ISSUE FEE	
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